

100

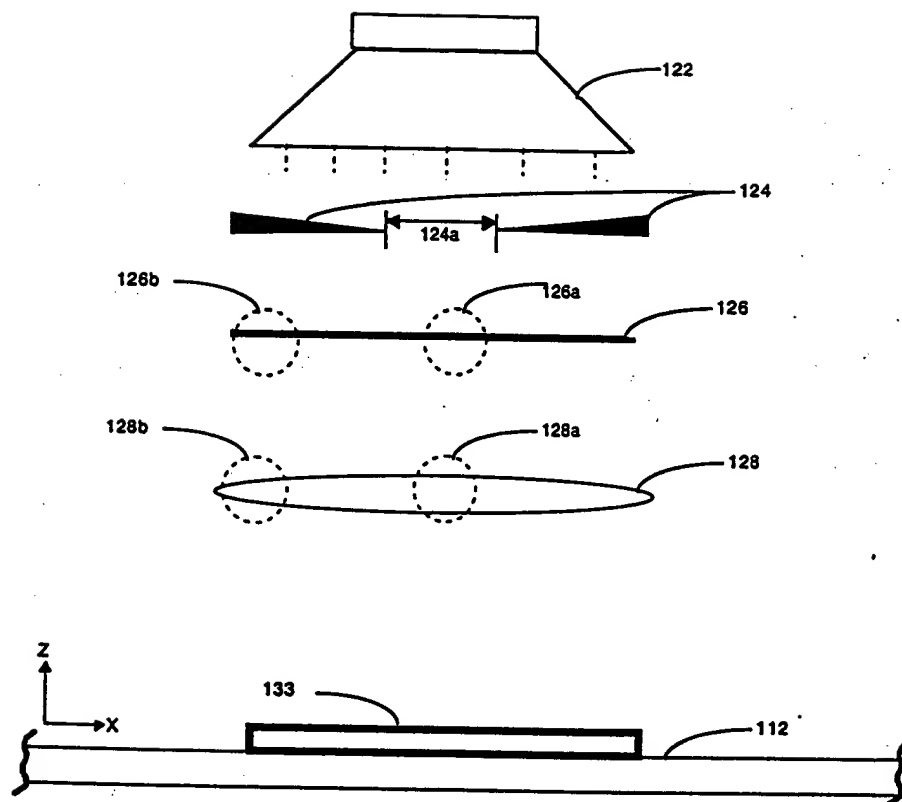


Figure 1
(Prior Art)

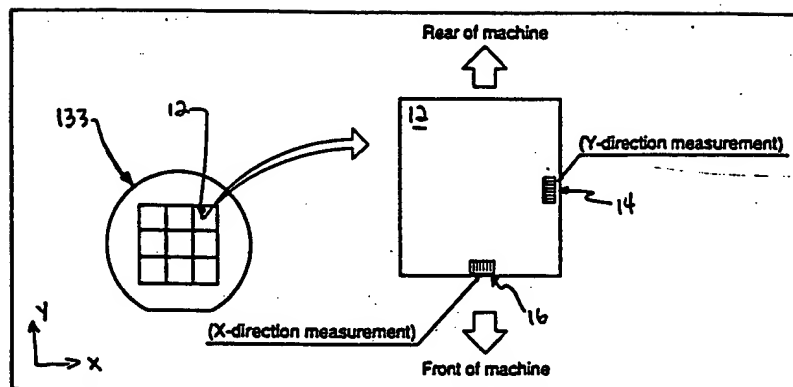


Figure 2A
(Prior Art)

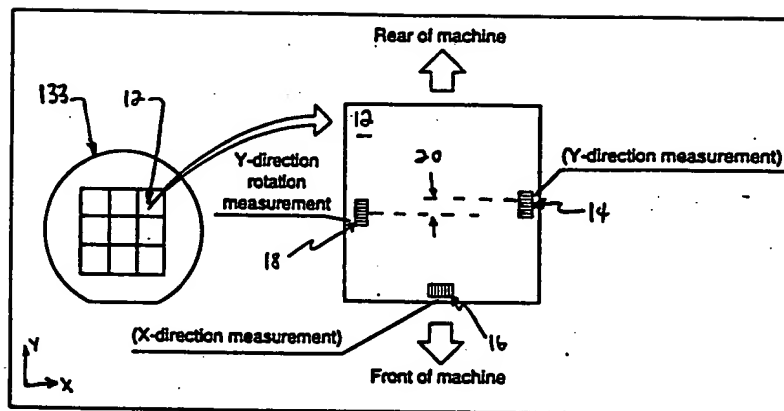


Figure 2B
(Prior Art)

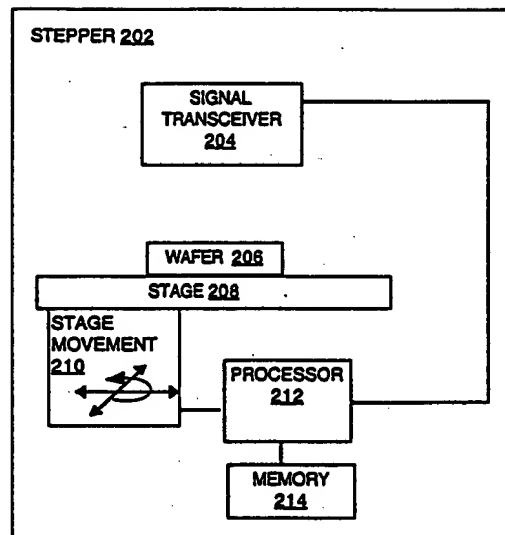


Figure 3

400

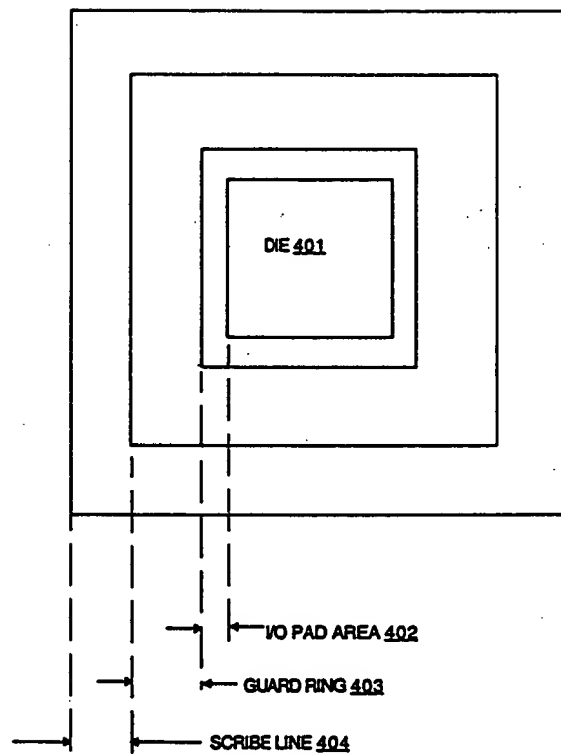


Figure 4A

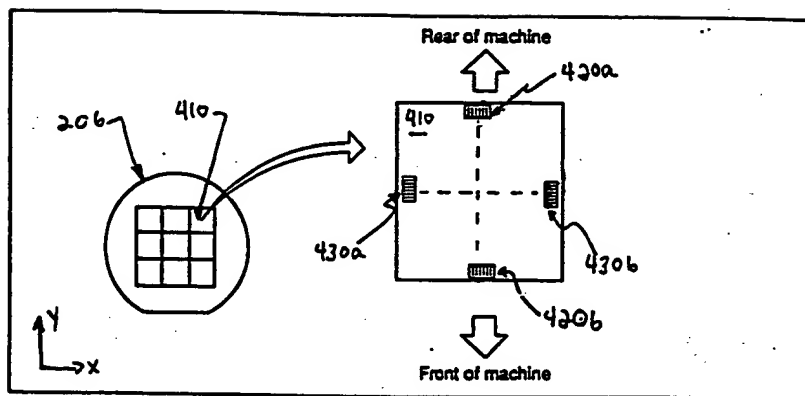


Figure 4B

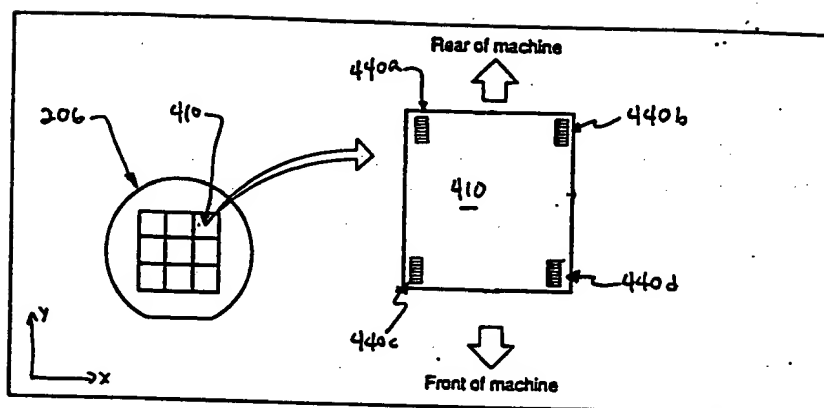


Figure 4C

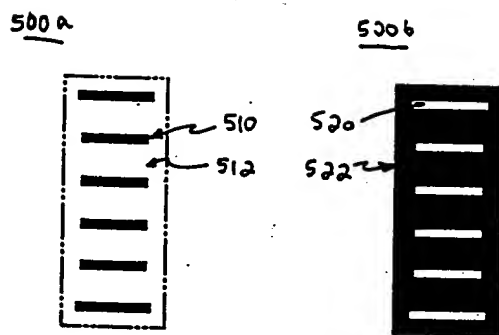


Figure 5

510

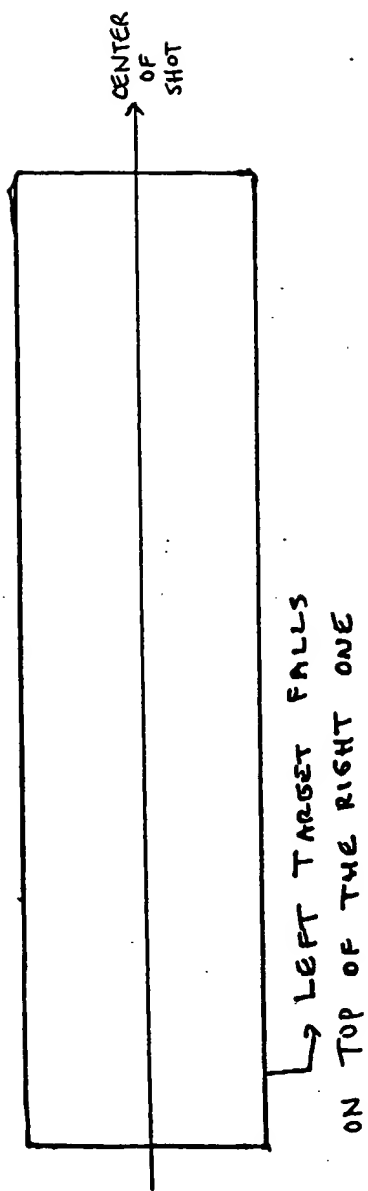


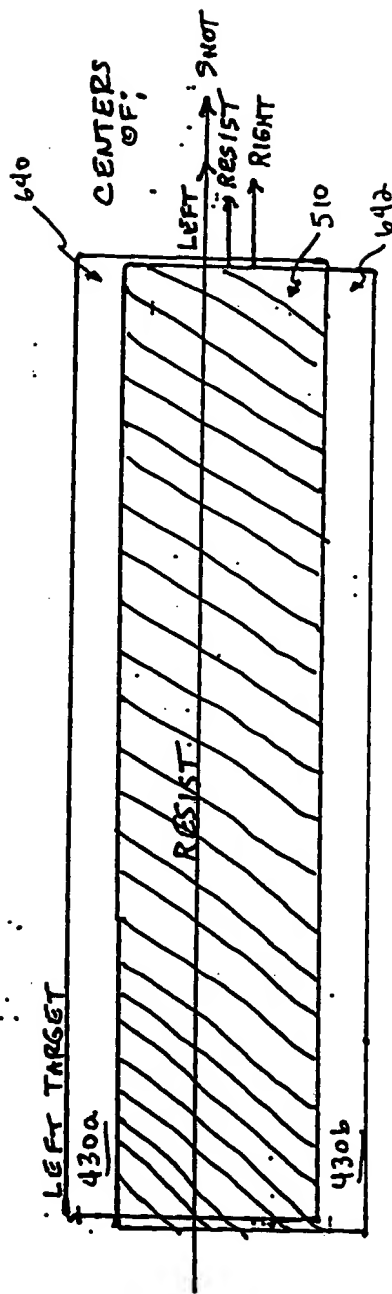
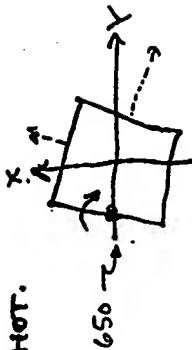
Figure 6A

A cross-sectional diagram of a substrate 630 with a central layer 510. The layer 510 is divided into two regions: a hatched region on the left labeled "LEFT TARGET" 430a and a white region on the right labeled "RIGHT TARGET" 430b. The hatched region contains the text "RESIST REMAINING AFTER DOUBLE EXPOSURE". Arrows labeled "LEFT" and "RIGHT" point to the left and right sides of the layer 510, respectively. An arrow labeled "SHOT" points to the right side of the layer 510.

THE CENTER OF THE RESIST
RECTANGLES WILL REMAIN COINCIDENT
WITH THE CENTER OF THE SHOT

Figure 6B

CW ROTATION ABOUT THE LEFT
CENTER OF THE SHOT.



THE CENTER LOCATION OF THE
RESIST RECTANGLE "FALLS" IN BETWEEN
THE CENTER OF THE SHOT AND THE
CENTER OF WHERE THE RIGHT RECTANGLE
"LANDED", SO THE ERROR IS CUT BY Y_2 .

Figure 6C

700

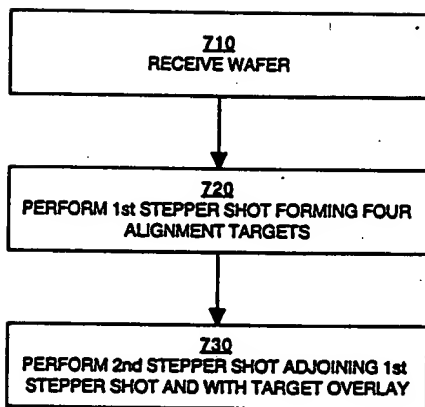


Figure 7

830

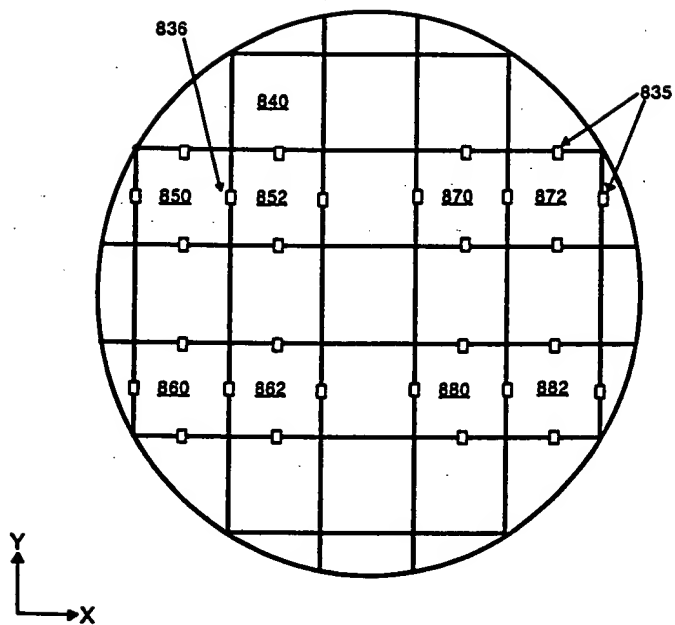


Figure 8